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REMARKS

Claims 11, 14, 21, 24, 31, 35, and 37 are amended. Claims 15, 16, 25, 28, 30, 32 - 34, 36 and 38 are cancelled. Claims 11, 14, 21, 22, 24, 27, 29, 31, 35 and 37 remain in the case.

Claims 11, 14 - 16 and 33 were objected to under 35 C.F.R. 1.75(c) as being of improper dependent form for failing to further limit the subject matter of a previous claim. In particular, the Examiner cited claim 11 reciting "a local clean room" indirectly dependent on a method claim 21; claim 14 dependent upon cancelled claim 10; claim 15 dependent upon cancelled claim 12; claim 16 dependent upon cancelled claim 13; and claim 33 dependent upon cancelled claim 26. Claim 11 has now been amended to require local clean equipment comprising a chemical filter and an air filter according to claim 27. Claim 11 requires that the local clean equipment has an air filter ultimately manufactured by the process as stated in claim 21. Therefore, claim 11 is a product by process claim. However, it should be noted that claim 21 has now been amended to place the terminology referring to the use of the air filter in the preamble.

Regarding claims 14, 15, 16 and 33, each of these claims were ultimately dependent upon now cancelled claims 26, 23 and 18. Amended claim 14 is now dependent upon claim 31. Claim 15, 16 and 33 are cancelled.

Claims 11, 21, 22, 24, 25, 27, 28, 29, 30 and 31 - 38 were rejected under 35 U.S.C. § 112, second paragraph as being indefinite for failing to particularly point out and distinctly claim the subject matter which Applicants regard as the invention. In particular, the Examiner states that claim 21 recites a series of manufacturing steps and limitations reciting "wherein the use of said air filter is the manufacture environment of a semiconductor device". The Examiner states that this claim is indefinite as the scope of the claim is uncertain. Claim 21 has now been amended to place the aforementioned terminology regarding the use of the air filter in the preamble.

The Examiner states that claim 24 is confusing because the Examiner is unsure as to what limitations claim 24 is dependent upon. The Examiner has

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suggested terminology to clarify the claim language. The Examiner's suggestion is appreciated and claim 24 has been amended to the Examiner's suggestion.

Claims 25, 28, 30, 32 - 34, 36 and 38 are cancelled.

Claim 31 has now been corrected to make it grammatically correct.

Claim 31 is now believed to be allowable.

Claims 11, 21, 22, 24, 25, 27, 28, 29, 30, 31, 32, 34, 35, 36, 37 and 38 were rejected under 35 U.S.C. § 101 because the claimed invention is directed to non-statutory subject matter. In claim 21, the method of using has been placed in the preamble of the claim to overcome the rejection under 35 U.S.C. § 101 for the aforementioned claims.

The Examiner states that claims 21 and 34 would be allowable if rewritten or amended to overcome the rejections under 35 U.S.C. § 112, second paragraph as set forth in this Office Action. The amendment to claim 21 should place this claim in condition for passing to issue. Further, dependent claims 11, 14, 22, 24, 27, 29, 31, 35 and 37 are ultimately dependent upon allowed claim 21 and are therefore now believed to be allowable also. Claim 34 is cancelled.

Since claims 25, 28, 30, 32, 36 and 38 are cancelled, the § 102(b) rejection is not addressed. This case is now believed in condition for passing to issue. Such action is requested.

Respectfully submitted,

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**VERSION WITH MARKINGS TO SHOW CHANGES MADE**

**In the claims:**

Please amend claims 11 and 14 as follows:

11. (Thrice Amended) [A local] Local clean equipment [having installed therein] comprising a chemical filter installed therein for trapping at least one of organic substances and inorganic substances and [also having installed therein] an air filter according to claim 27 installed therein for trapping suspended particulate substances in the air, said air filter being installed downstream of said chemical filter[, characterized in that; an air filter according to claim 27 is installed as said air filter].

14. (Amended) [A local facility] Local clean equipment as defined in claim [10] 31 which comprises a clean bench, a clean booth, a wafer stocker, wafer transfer space, and semiconductor fabrication equipment.

Please cancel claims 15, and 16.

Please amend claims 21 and 24 as follows:

21. (Amended) A method for manufacturing a filter medium for an air filter to be used in the manufacture environment of a semiconductor device, comprising [a step] the steps of forming a non-woven fabric by binding fibers by a binder, [characterized in that:]

said binder having its chief ingredient of a polymer dispersion having a copolymer of a hydrophilic monomer and a hydrophobic monomer dispersed in water, and

obtaining said polymer dispersion [obtained] by a polymerization step of dissolving the hydrophilic monomer in water, adding the hydrophilic monomer to this water solution and dispersing said hydrophobic monomer in said water solution, and adding a polymerization initiator to form said copolymer,

wherein in said polymerization step, a hydrophilic organic peroxide of cumen hydroperoxide, 2, 5-dimethylhexan-2, 5-hydroperoxide, or succinic acid

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peroxide is used as a polymerization initiator[, and wherein the use of said air filter is the manufacture environment of a semiconductor device].

24. (Amended) A filter medium [for an air filter] manufactured by [a] the method [for manufacturing a filter medium for an air filter according to] of claim 21.

Please cancel claims 25, 28, and 30.

Please amend claim 31 as follows:

31. (Amended) [A local] Local clean equipment having an air filter according to claim 27 installed therein.

Please cancel claims 32, 33, and 34.

Please amend claim 35 as follows:

35. (Amended) A method for manufacturing semiconductors, wherein a silicon wafer for said semiconductor is processed in at least one of a clean room and [a local facility] local clean equipment having an air filter as defined in claim 27.

Please cancel claim 36.

Please amend claim 37 as follows:

37. (Amended) A semiconductor device made by processing a silicon wafer in at least one of a clean room and [a local facility] local clean equipment having an air filter as defined in claim 27.

Please cancel claim 38.